

S2 1 PN="2000-066075"
?t 2/5/1

2/5/1

DIALOG(R) File 347:JAPIO
(c) 2001 JPO & JAPIO. All rts. reserv.

06480498 **Image available**
OPTICAL SYSTEM AND ITS PRODUCTION AND EXPOSURE DEVICE EQUIPPED WITH THE
OPTICAL SYSTEM

PUB. NO.: 2000-066075 [JP 2000066075 A]
PUBLISHED: March 03, 2000 (20000303)
INVENTOR(s): SHIGEMATSU KOJI
TANAKA KAZUMASA
HATAZAWA MASATO
APPLICANT(s): NIKON CORP
APPL. NO.: 10-230639 [JP 98230639]
FILED: August 17, 1998 (19980817)
INTL CLASS: G02B-007/02; G02B-013/24; G03F-007/20; H01L-021/027

ABSTRACT

PROBLEM TO BE SOLVED: To provide an optical system equipped with plural optical members and capable of obtaining high optical characteristic (image-formation performance or the like).

SOLUTION: The image of the pattern of a reticle 12 is projected and exposed to a wafer 14 through a projection optical system having lenses 3A and 3B. Assuming that the lenses 3A and 3B are held by three-point supporting system holding members 4A and 4B, after the deformation amount of the respective lenses in the case of holding the lenses by members 4A and 4B is obtained (1st stage), the residual aberration of the projection optical system due to the deformation amount is obtained (2nd stage). Then, the rotational angles of the members 4A and 4B are optimized so that the residual aberration may be small (3rd stage) and the rotational angles of the members 4A and 4B in the projection optical system 1 are adjusted to the rotational angles optimized in such a way (4th stage).

COPYRIGHT: (C)2000,JPO